



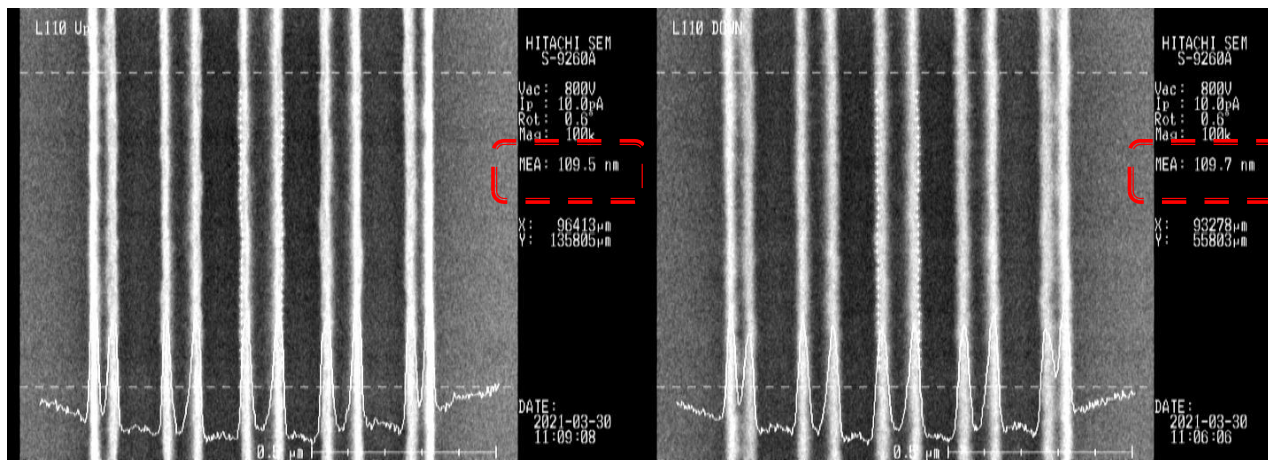
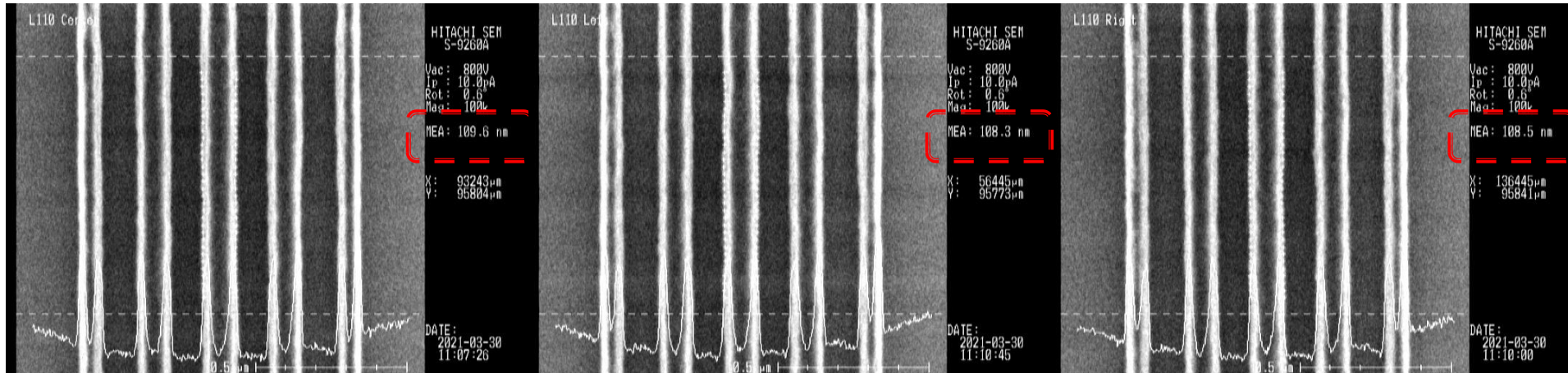
**NAR Labs** National Applied Research Laboratories  
Taiwan Semiconductor Research Institute

# L22 高速量產型光學曝光系統 技術資料 (248 Scanner Technology Data)

負責工程師: 黃才銘  
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# GKR-5201A 解析度

1. Substrate: 雙拋 Silicon Wafer
2. 光阻: GKR-5201A (3160Å)
3. 光罩: Binary Mask
4. 線寬設計 Line/Space: 110/110 nm



Location	Linewidth (nm)
Center	109.6
Left	108.3
Right	108.5
Up	109.5
Down	109.7

# TDUR-P6159 解析度

1. Substrate: 雙拋 Silicon Wafer
2. 光阻: TDUR-P6159 (8000Å/20000Å)
3. 光罩: Binary Mask

248	P6159	
PR Thickness (A)	8000	
Resolution	Line/Space: 0.25 um	Hole/Pillar: 0.35 um
		Line/Space: 0.8 um Dense Hole/Pillar: 1 um

